



ABSTRACT

SUBSTRATE PROCESSING APPARATUS AND SUBSTRATE PROCESSING
METHOD.

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A substrate processing apparatus is disclosed, comprising:

a main transfer section for transferring a substrate:

temperature regulating sections, disposed around said main transfer section in at least

10 two directions facing each other out of four directions, for receiving and sending the
substrate from/to said main transfer device and regulating the temperature of the
substrate at a predetermined temperature:

a thermal processing section for processing the substrate at a temperature not less than
the predetermined temperature; and

15 moving means for moving said temperature regulating section to deliver the substrate
from/to said temperature regulating section to/from said thermal processing section.

Fig. 1